

Magnetic Shielded Sputter Gun

VIBRATION ISOLATOR & CHAMBER PRODUCTS



Magnetic Shields enable the RHEED measurement in the same chamber

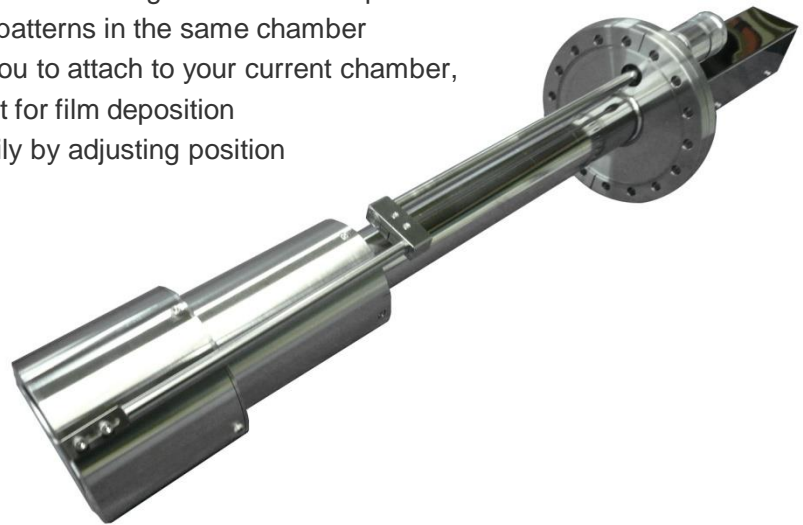
Small sized, Low cost, Attachable to the current chamber

Feature

- Applicable to various targets such as metal, insulator, magnetic material, or non-magnetic material
- VIC ϕ Film Deposition Chamber which installs Magnetic Shielded Sputter Gun enables you to measure the RHEED patterns in the same chamber
- The flange mount structure enables you to attach to your current chamber, then provides you kinds of experiment for film deposition
- Erosion adjustment is carried out easily by adjusting position or exchanging for internal magnet

Application:

- Film Coating
- Semiconductor Device
- Superconductor Film
- MEMS



Specification

Target Size	$\phi 50.8 \times 3$ mm
Sputter discharge pressure	50 Pa ~ 0.5 Pa
Discharge Method RF (13.56MHz)	300W MAX
Earth-cover	$\phi 80 \times 72$ mm 78 Permalloy (magnetic annealing)
Fitting Flange	ICF152 * Kinds of flanges available.
Length	640 mm (± 50 mm)
Length from flange to end point	370 mm (± 50 mm)
Shutter	$\phi 76$ mm 78 Permalloy (magnetic annealing)
Shutter Structure	Swing, Z direction moving (for magnetic shielding)
Cooling Water	3 L / MIN
Baking Temperature	110°C
Optional	Power Supply for RF300W/DC500W Auto tuning of matching BOX Z axis stage Normal Magnetron Sputter Gun

RHEED picture with installed Sputter Gun

Pressure : 5.8×10^{-6} Pa
RHEED output : 25Kv 2 A
Substrate : C-AL 203
Incident Azimuth : 10-10

